



TAL
TECH

FABRICATION 2

LECTURE 6

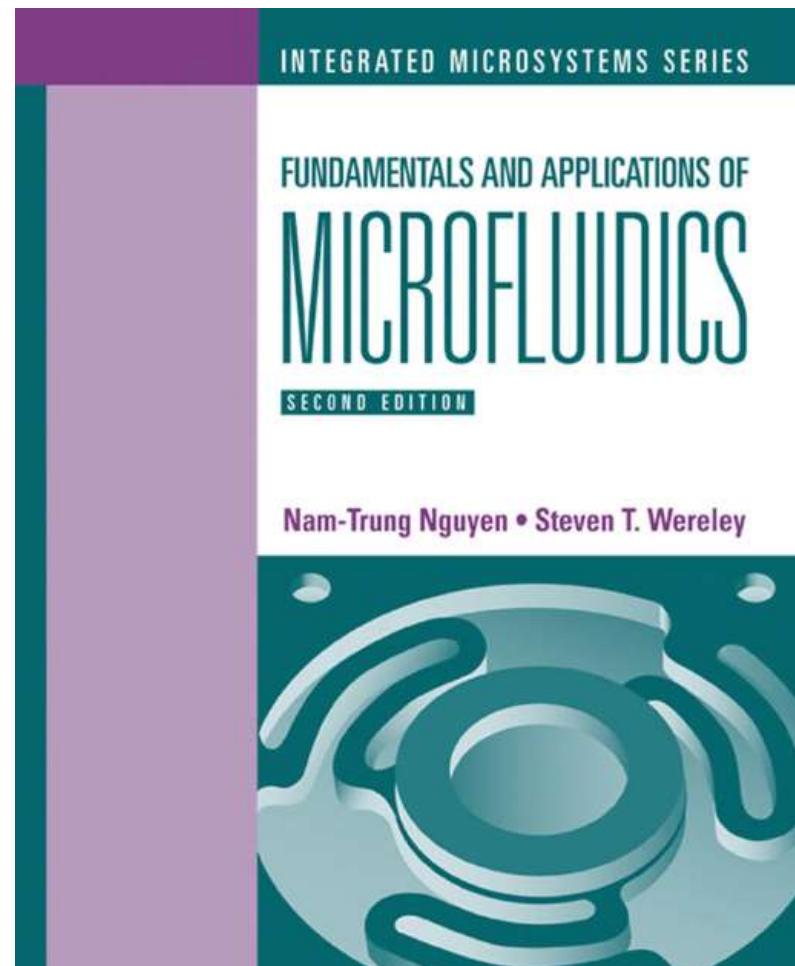
Tamás Pardy
TalTech Lab-on-a-Chip

13.01.2022

TALLINN UNIVERSITY
OF TECHNOLOGY

BEFORE WE BEGIN...

- Fundamentals and Applications of Microfluidics (2nd edition) – **Chapter III**
- Nam-Trung Nguyen, Steven T. Wereley
- ISBN-10 1-58053-972-6
ISBN-13 978-1-58053-972-2



OVERVIEW



INDUSTRIAL FABRICATION

- Hot embossing
- Injection molding

13.01.2022



MICROFABRICATION

- Clean rooms
- Materials

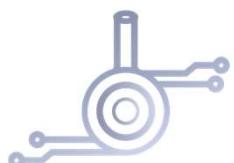
13.01.2022



MICROFABRICATION PROCESSES

- Additive processes
- Subtractive processes
- Photolithography and lift-off
- Soft lithography

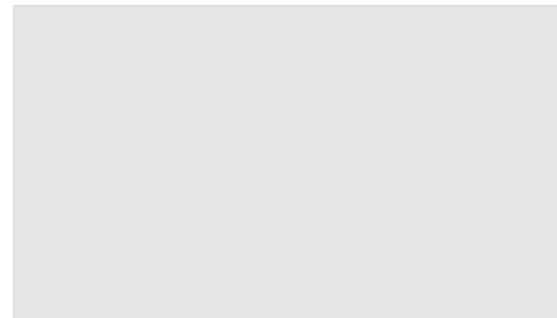
13.01.2022



COMMERCIAL EXAMPLES

- Immunoassays
- Nucleic acid amplification tests

13.01.2022





INDUSTRIAL FABRICATION

- Hot embossing
- Injection molding

13.01.2022

INTRODUCTION: MICROFLUIDIC SETUPS

++Level of Integration
↓

1. Traditional flow chemistry setup

- Professional analytical laboratories, including medical diagnostics (**chip in a lab**)
- Target: lower cost OR better volume control
- Expensive instrumentation but cheap assay



1.

2. Cartridge + reader

- Point-of-Care/Point-of-Need analytics
- Target: wider availability
- Mid-range instrumentation cost, mid-range assay cost



2.



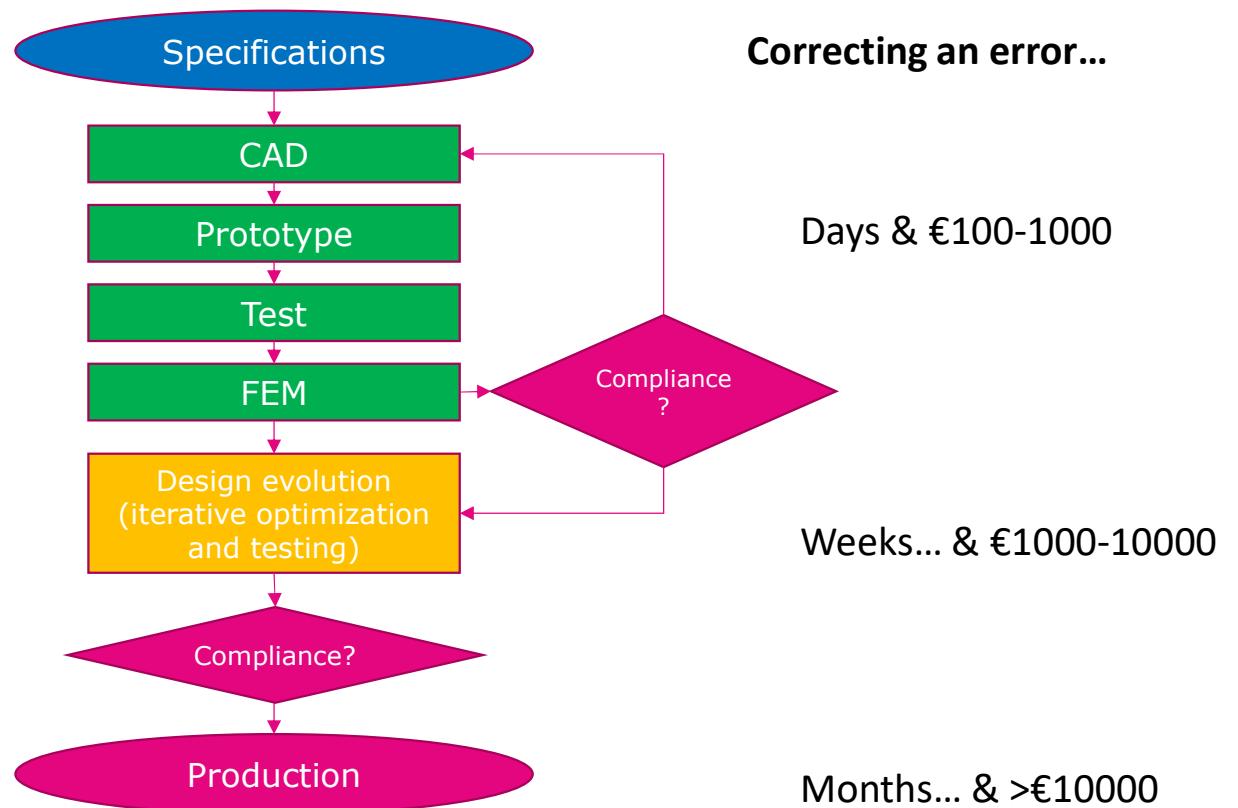
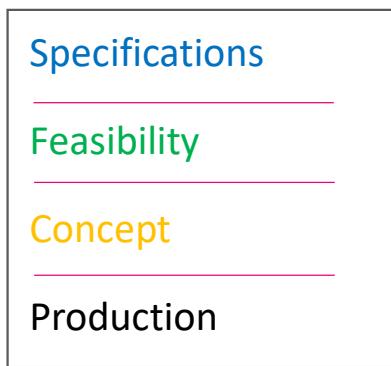
3.

3. Fully integrated (true **lab-on-a-chip**)

- Homecare diagnostics
- Target: home & office diagnostics
- Low instrument cost, high assay cost

13.01.2022

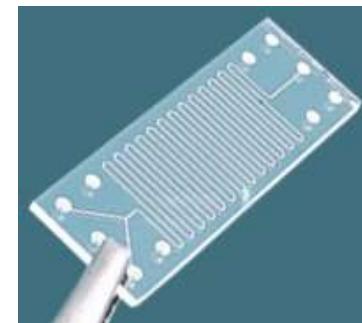
COMPUTER-AIDED ENGINEERING



http://web.mit.edu/16.810/www/16.810_L4_CAE.pdf

FABRICATION TECHNIQUES FOR POLYMERS

- Why polymers?
 - **Cheap (max. 1-2 EUR per chip)**
 - Easy to machine
 - Optically transparent (if needed)
 - Good thermal and electrical properties
 - High aspect-ratio for microstructures
 - Biocompatible (if needed)
 - Recyclable options available
- **Plastics are particularly well-suited for single-use rapid tests (e.g. pregnancy test)**



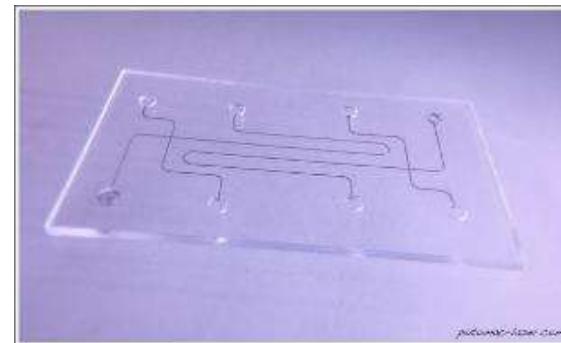
<https://syntecoptics.com/polymer-optics-microfluidics/polymer-microfluidic-devices>



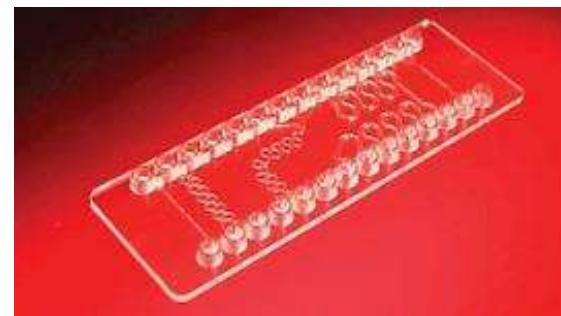
https://en.wikipedia.org/wiki/HCG_pregnancy_strip_test

FABRICATION TECHNIQUES FOR POLYMERS

- PMMA (Polymethyl methacrylate)
 - Transparent thermoplastic
 - Chemically resistant, mechanically robust
 - Good for hot embossing (see later) and milling
- COC (Cyclic olefin copolymer)
 - Chemically resistant, mechanically robust
 - Good for injection moulding (see later)



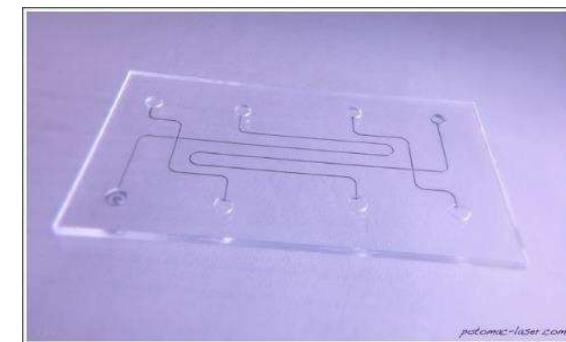
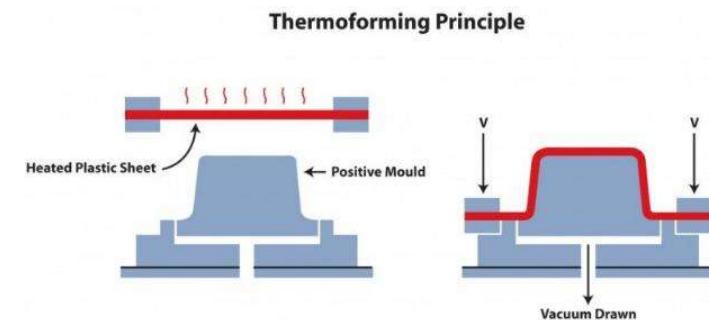
Property	Value
ϵ	4.9
Melting point	160 °C
k	0.18 W/(mK)
ρ	2e15 Ω cm



Property	Value
ϵ	2.35
Melting point	75-170 °C
k	0.12-0.15 W/(mK)
ρ	1e15 Ω m

FABRICATION TECHNIQUES: HOT EMBOSSED

- **Hot embossing (microthermoforming)**
process of forming heated plastic sheets to a specific shape using a mould.
- **Animation:** [link](#)
Video: <https://youtu.be/GcWD9AP6f8U?t=32>
- **Input:** patterned positive master mould
Output: patterned plastic sheet/ polymer layer
- **Thermoplastic nanoimprint lithography (T-NIL)**
hot embossing in nanoscale, but instead of a plastic sheet, a thermoplastic polymer layer is imprinted.



FABRICATION TECHNIQUES: INJECTION MOULDING

- **Injection moulding:**

- process by which material is formed by injection into a mould. The material is fed into the mould cavity through a heated barrel at high pressure.

- **Video:** <https://youtu.be/b1U9W4iNDiQ?t=22>

- **The mould is machined from metal**

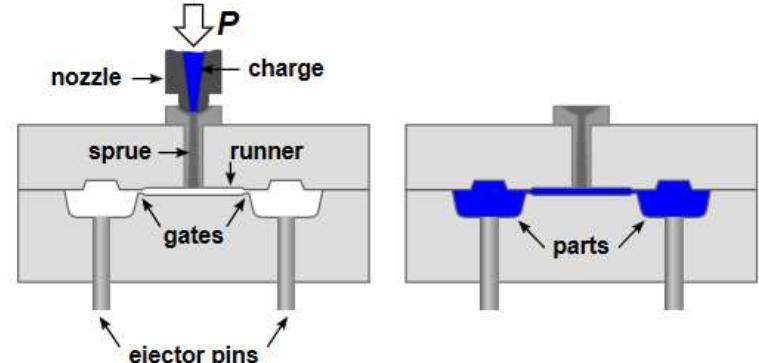
- Steel for mass production (>1 M)
- Aluminium for small-series production (10k)

- **Not suitable for prototyping!**

- **Injection moulding is not suitable for prototyping!**
A mould typically costs on the order of 100kEUR, so any design change is ill-advised.

- **Input:** machined metal mould

Output: injection moulded plastic part



https://en.wikipedia.org/wiki/Injection_moulding



https://cdn.technologyreview.com/i/legacy/sia_x600.jpg

FABRICATION TECHNIQUES: COMPARISON

	Milling	Hot embossing	Injection moulding
Mould cost	0	\$ or \$\$	€10-100k
Cost/pc (mass- production)	€10-100	\$\$	€<1
Best applied for	Prototyping	Prototyping and production	Production only
Typical chip layer structure	Multilayer	Multilayer	Monolithic
Minimum feature size	2.5-7.5 µm	<100 nm (via NIL)	50-100 nm



INDUSTRIAL FABRICATION

- Hot embossing
- Injection molding

13.01.2022



MICROFABRICATION

- Clean rooms
- Materials

13.01.2022

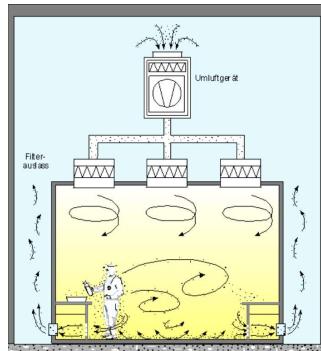
1. INTRODUCTION: CLEAN ROOM

Clean room = facility utilized as part of specialized industrial production or scientific research, including the manufacture of pharmaceutical items and microprocessors

Clean room air has low levels of particulates (standard: ISO 14644-1)

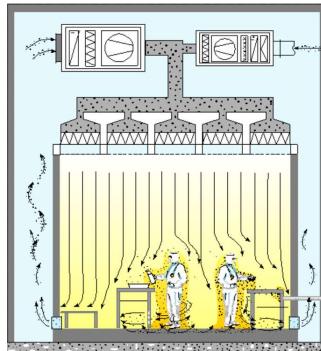


Turbulent



https://en.wikipedia.org/wiki/Cleanroom#/media/File:Laminar_Flow_Reinraum.png

Laminar



Class	Maximum particles/m ³ ^a						FED STD 209E equivalent
	≥0.1 µm	≥0.2 µm	≥0.3 µm	≥0.5 µm	≥1 µm	≥5 µm	
ISO 1	10 ^b	d	d	d	d	d	e
ISO 2	100	24 ^b	10 ^b	d	d	d	e
ISO 3	1,000	237	102	35 ^b	d	e	Class 1
ISO 4	10,000	2,370	1,020	352	83 ^b	e	Class 10
ISO 5	100,000	23,700	10,200	3,520	832	d,e,f	Class 100
ISO 6	1,000,000	237,000	102,000	35,200	8,320	293	Class 1,000
ISO 7	c	c	c	352,000	83,200	2,930	Class 10,000
ISO 8	c	c	c	3,520,000	832,000	29,300	Class 100,000
ISO 9	c	c	c	35,200,000	8,320,000	293,000	Room air

^a All concentrations in the table are cumulative, e.g. for ISO Class 5, the 10 200 particles shown at 0.3 µm include all particles equal to and greater than this size.

^b These concentrations will lead to large air sample volumes for classification. Sequential sampling procedure may be applied; see Annex D.

^c Concentration limits are not applicable in this region of the table due to very high particle concentration.

^d Sampling and statistical limitations for particles in low concentrations make classification inappropriate.

^e Sample collection limitations for both particles in low concentrations and sizes greater than 1 µm make classification at this particle size inappropriate, due to potential particle losses in the sampling system.

^f In order to specify this particle size in association with ISO Class 5, the microparticle descriptor M may be adapted and used in conjunction with at least one other particle size. (See C.7.)

<https://en.wikipedia.org/wiki/Cleanroom>

Clean room air is kept clean by continuously recirculating and filtering air in the room through HEPA or ULPA filters.

In laminar flow layouts, air comes from the ceiling and is recirculated through floor vents, taking away any particulates in the process.

1. INTRODUCTION: CLEAN ROOM



<https://www.terrauniversal.com/cleanrooms/cleanroom-airlock.php>

See the metal mesh?
That's for **antistatic**
protection.

Entry is usually through an **airlock with an air shower** stage
Protective clothing (face mask, gloves, shoes, coat) must be worn inside.



https://en.wikipedia.org/wiki/File:Cleanroom_outside.jpg

Yellow light prevents unwanted exposure of **photosensitive** polymers.



**TAL
TECH**

TALLINN UNIVERSITY
OF TECHNOLOGY

13.01.2022

1. INTRODUCTION: CLEAN ROOM

- **Clean rooms are expensive:**

- It's all pretty cool but it's hellishly expensive, right? Right, unfortunately... \$1-10k/m²
- We don't have a clean room at TJS ELIN yet. A cheaper alternative, which is just as good but smaller: **glovebox**

- **Gloveboxes are more accessible:**

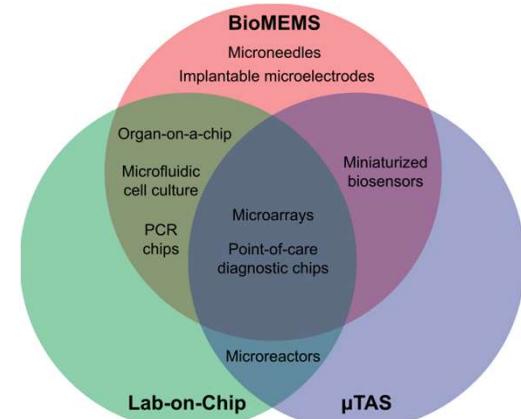
- sealed container designed to allow manipulation of objects in a separate atmosphere.
- Usually an inert gas such as nitrogen or argon is used to fill the glove box at positive pressure.
- Pressure is maintained during work and in case of leaks, the positive pressure keeps contaminants out.
- Good enough for Lab-on-a-Chip, costs 5-20k€ used.



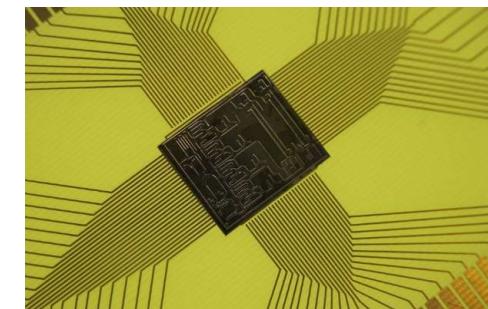
<https://www.cysi.wang/glove-box/800.html>

1. INTRODUCTION: MICROFABRICATION

- **Microfabrication**: process for the production of devices in the submicron to millimeter range.
- **MEMS** (Microelectromechanical systems): microscopic devices, esp. with moving parts. Components in range 1-100 μm , device in range 20 μm – 1 mm.
- **BioMEMS**: biomedical MEMS.
- **μTAS** =micro total analysis system
- **Lab-on-a-Chip**
 - it all started in a clean room in 1979 (S.C. Terry, Stanford University) with a gas chromatograph...
 - (analytical chemistry drove LoC for a long time, then it turned towards diagnostics)



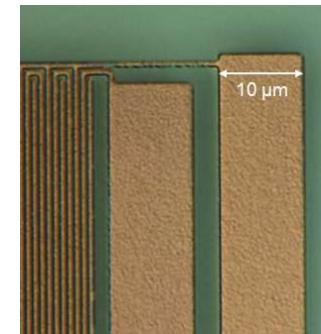
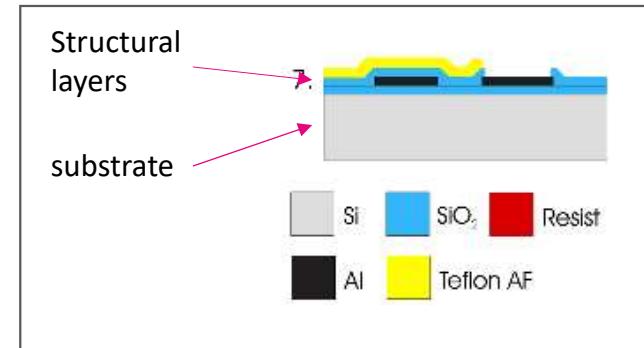
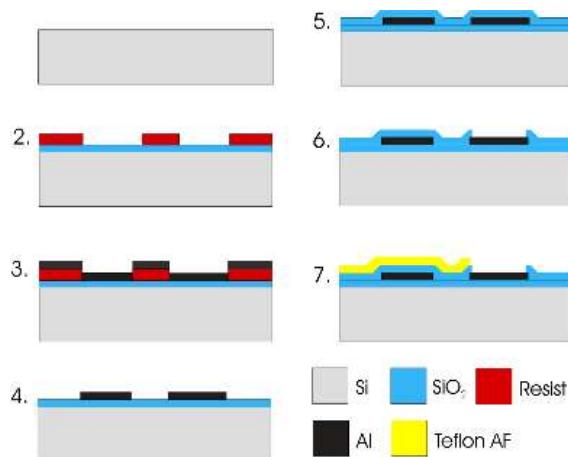
<https://en.wikipedia.org/wiki/Bio-MEMS>



<https://en.wikipedia.org/wiki/File:Labonachip20017-300.jpg>

1. INTRODUCTION: MICROFABRICATION

- **Substrate**: the physical material upon which the device is built (~underlayer)
- **Thin film**: few nanometer to micrometer thick material layer
- Example for microfabrication process steps:



By MBirkholz - Own work, CC BY-SA 4.0,
<https://commons.wikimedia.org/w/index.php?curid=59803833>

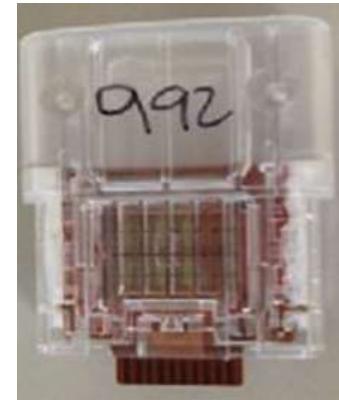
1. INTRODUCTION: MICROFABRICATION

▪ Pros:

- Microfabrication yields structures with high aspect ratios
- Good for feature sizes under 100 μm , ideal under 10 μm
- Wide material selection, high production quality and good process control
- Integration of electronics in the chip
- Cheap in large quantities

▪ Cons:

- Very expensive to prototype and upscale
- Is 'clean industry' but uses hazardous chemicals and gases
- Instrumentation is hellishly expensive (>1M€ to set up a clean room with some instrumentation)

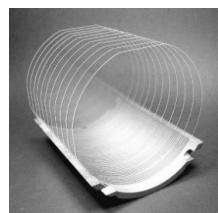


<https://www.nature.com/articles/srep36000/figures/1>

This level of integration is only possible via microfabrication but the barrier to entry is too high for startups

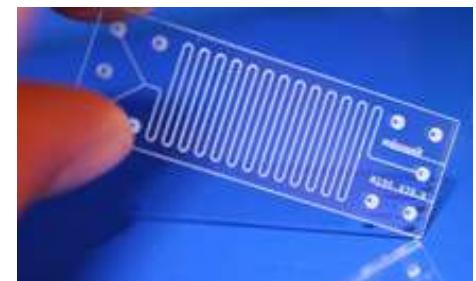
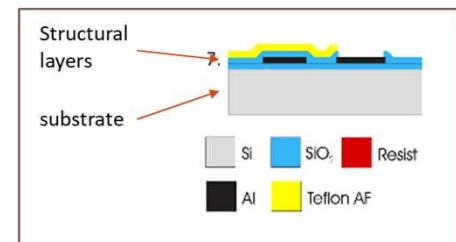
2. SUBSTRATES AND STRUCTURAL MATERIALS

- Substrate options



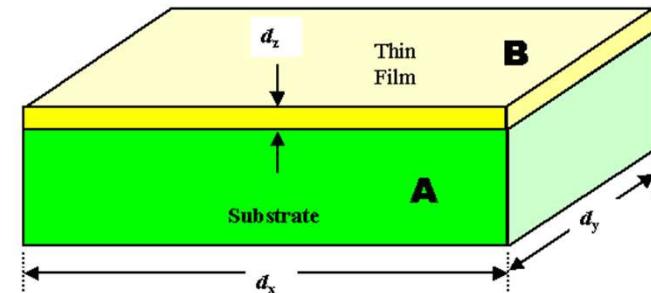
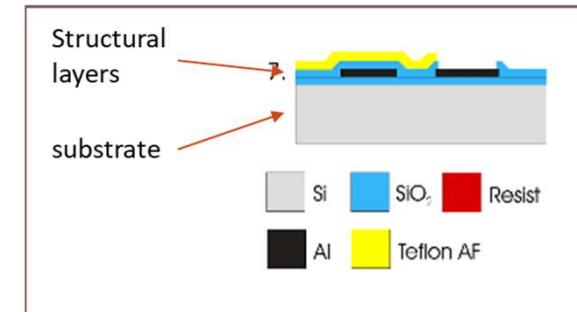
	Silicon	Glass
Pros	Resistant to organic solvents, good thermal conductivity	Chemically resistant, transparent
Cons	Expensive, not transparent	Expensive, permeable to gas

Typically silicon-silicon or glass-glass chips



2. SUBSTRATES AND STRUCTURAL MATERIALS

- **Structural materials are typically deposited as thin films**
- **Most commonly used thin films are:**
 - Silicon dioxide (SiO_2)
 - Thermal oxide or CVD oxide (we'll talk about these later)
 - Electrical insulation, mask, sacrificial layer
 - Silicon Nitride (Si_3N_4)
 - Electrical insulation between conductive layers
 - Highly selective etching
 - Structural support
 - Metal films (e.g. aluminum, gold, platinum)
 - Conductive tracks, electrodes etc.
 - Aluminum used as optically reflective layer
 - Transparent conducting films (TCF)
 - Indium tin oxide (ITO)
 - Carbon nanotube



https://www.tf.uni-kiel.de/matlwis/amat/semitech_en/kap_3/backbone/r3_2_2.html

13.01.2022

1/13/2022



MICROFABRICATION

- Clean rooms
- Materials

13.01.2022



MICROFABRICATION PROCESSES

- Additive processes
- Subtractive processes
- Photolithography and lift-off
- Soft lithography

13.01.2022

3. MICROFABRICATION PROCESSES

Additive processes

3D printing

Jet printing (e.g. FDM)
Selective photopolymerization (SLA, DLP)
Selective sintering (SLS)

Layer deposition

Mostly thin film deposition
Vapor phase deposition (PVD, CVD)
Liquid phase deposition (spin coating)



Subtractive processes

Surface micromachining

thin films are deposited **on the substrate** and micromachined (e.g. lift- off process)

Bulk micromachining:

the bulk of the **substrate** is micromachined

3. ADDITIVE PROCESSES

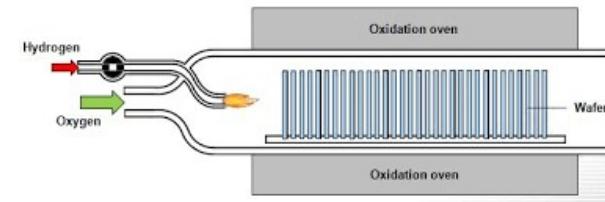
- Physical deposition (vapor-phase):
 - Thermal oxidation
 - Evaporation
 - Sputtering
 - Arc vapor deposition
 - Laser ablation
 - Ion plating
- Liquid phase deposition
 - Spin coating or dip coating
 - Chemical vapor deposition (CVD)
 - Plasma enhanced CVD
 - Atmospheric pressure CVD
 - Low-Pressure CVD
- Epitaxy

This is the arsenal, but we only focus on the ones most relevant to BioMEMS

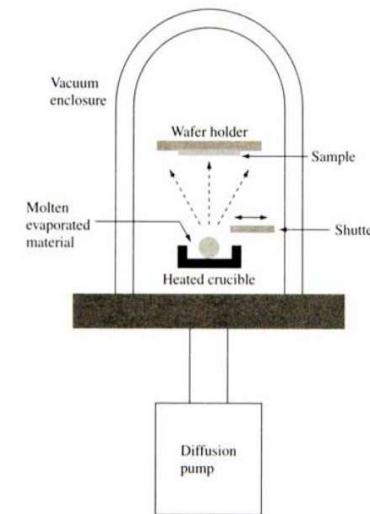
3. ADDITIVE PROCESSES

- **Physical deposition (vapor-phase):**
 - Thermal oxidation
 - Evaporation
 - Sputtering
 - Arc vapor deposition
 - Laser ablation
 - Ion plating
- Liquid phase deposition
 - Spin coating or dip coating
 - Chemical vapor deposition (CVD)
 - Plasma enhanced CVD
 - Atmospheric pressure CVD
 - Low-Pressure CVD
- Epitaxy

High Temperature Oxide layer (HTO) 800-1200 °C
With water/oxygen with/without HCl



<http://Inf-wiki.eecs.umich.edu/wiki/File:Thermal.png>

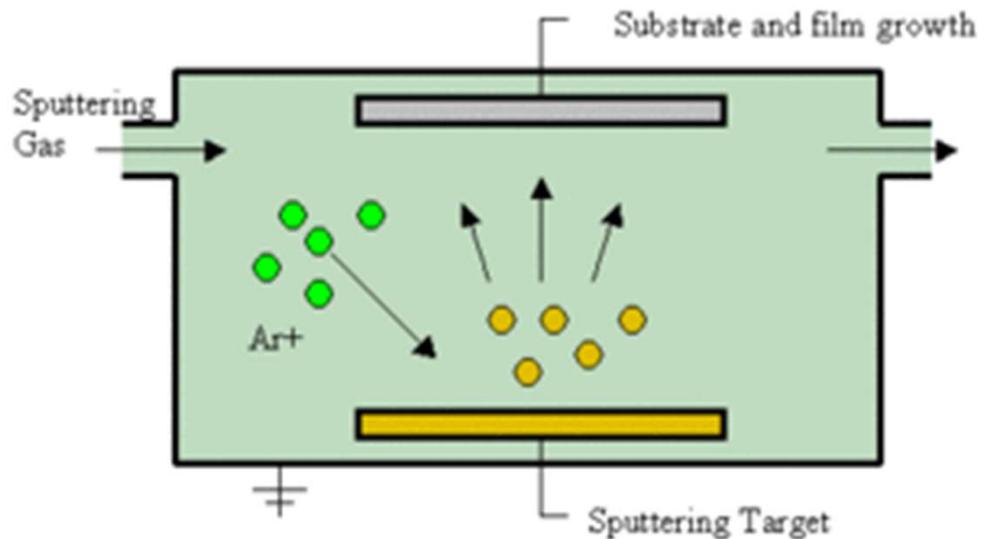


Gardner JW et al, Microsensors, MEMS and Smart Devices, 2001

Evaporation of source material in vacuum

3. ADDITIVE PROCESSES

- Physical deposition (vapor-phase):
 - Thermal oxidation
 - Evaporation
 - **Sputtering (deposition)**
 - Arc vapor deposition
 - Laser ablation
 - Ion plating
- Liquid phase deposition
 - Spin coating or dip coating
 - Chemical vapor deposition (CVD)
 - Plasma enhanced CVD
 - Atmospheric pressure CVD
 - Low-Pressure CVD
- Epitaxy



[This Photo](#) by Unknown Author is licensed under [CC BY-SA](#)

Sputtering = ejection of microparticles from surface of a solid upon bombardment with high-energy plasma/gas

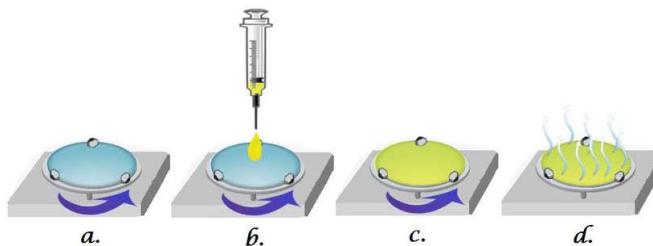
(Re-)sputtering: physical vapor deposition in plasma

Sputtering gas = Inert gas plasma

Eroding from target → depositing on substrate

3. ADDITIVE PROCESSES

- Physical deposition (vapor-phase):
 - Thermal oxidation
 - Evaporation
 - Sputtering
 - Arc vapor deposition
 - Laser ablation
 - Ion plating
- Liquid phase deposition
 - **Spin coating or dip coating**
 - Chemical vapor deposition (CVD)
 - Plasma enhanced CVD
 - Atmospheric pressure CVD
 - Low-Pressure CVD
- Epitaxy



https://www.researchgate.net/figure/Spin-coating-process-of-polyamide-6-thin-films_fig3_311616041

We have a POLOS SPIN150i

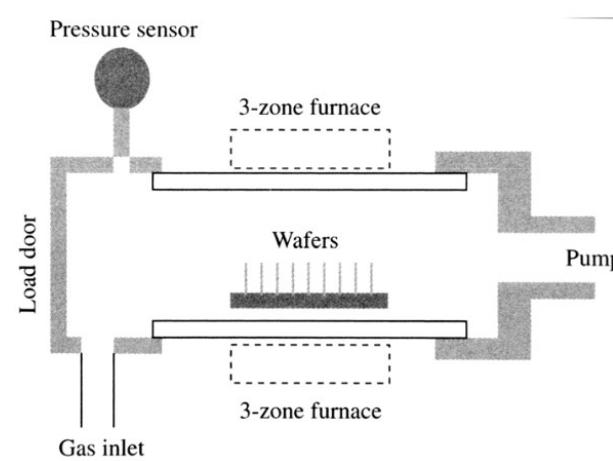
- Wafer size 5-450 mm
- Speed 1-12k RPM



<https://www.spincoating.com/>

3. ADDITIVE PROCESSES

- Physical deposition (vapor-phase):
 - Thermal oxidation
 - Evaporation
 - Sputtering
 - Arc vapor deposition
 - Laser ablation
 - Ion plating
- Liquid phase deposition
 - Spin coating or dip coating
 - **Chemical vapor deposition (CVD)**
 - Plasma enhanced CVD
 - Atmospheric pressure CVD
 - Low-Pressure CVD
- Epitaxy



Typically, CVD done in vacuum. Produces high-quality thin films

Gardner JW et al, Microsensors, MEMS and Smart Devices, 2004

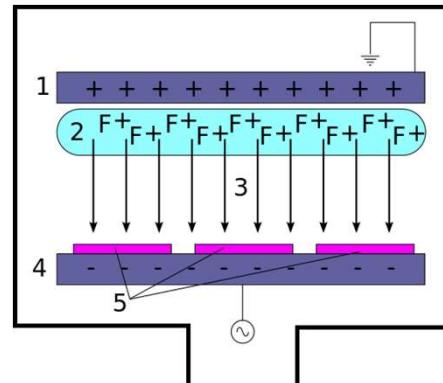
3. SUBTRACTIVE PROCESSES

- Dry etching (plasma):
 - Glow discharge methods (diode setups):
 - Plasma etching (PE),
 - Reactive ion etching (RIE),
 - Ion beam methods (triode setups):
 - Ion beam milling (IBM),
 - Reactive ion beam etching (RIBE),
 - Chemical assisted ion beam etching (CAIBE).
 - Deep Reactive Ion Etching (DRIE).
- Wet etching (chemical liquids).

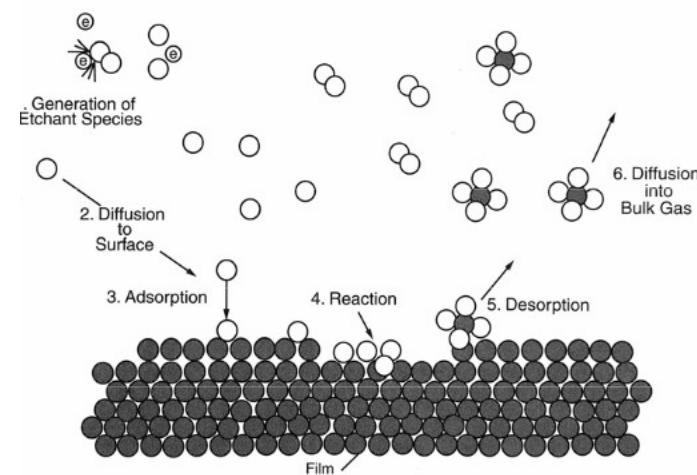
This is the arsenal, but we only focus on the ones most relevant to BioMEMS

3. SUBTRACTIVE PROCESSES

- Dry etching (plasma):
 - **Glow discharge methods (diode setups):**
 - Plasma etching (PE),
 - Reactive ion etching (RIE),
 - Ion beam methods (triode setups):
 - Ion beam milling (IBM),
 - Reactive ion beam etching (RIBE),
 - Chemical assisted ion beam etching (CAIBE).
 - Deep Reactive Ion Etching (DRIE).
- Wet etching (chemical liquids).



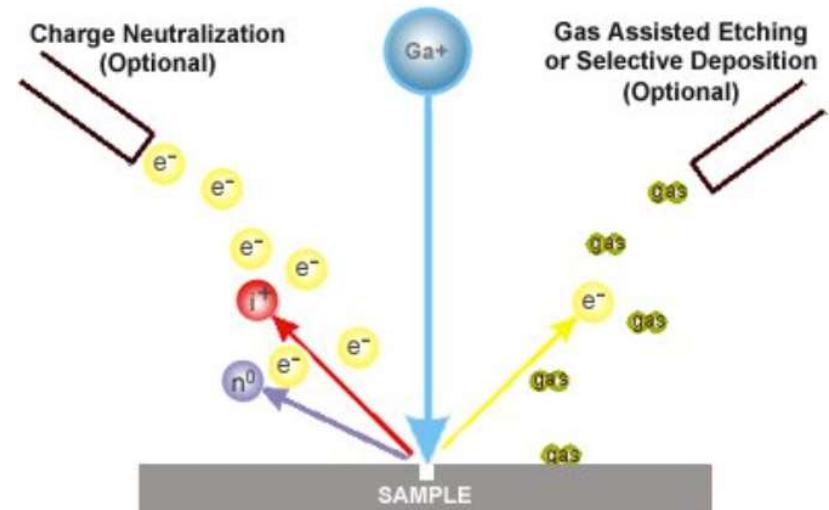
RIE: Electrodes 1), 4) create electric field 3), accelerating ions 2) toward sample surface 5)



Madou M, Fundamentals of Microfabrication, 2002

3. SUBTRACTIVE PROCESSES

- Dry etching (plasma):
 - Glow discharge methods (diode setups):
 - Plasma etching (PE),
 - Reactive ion etching (RIE),
 - **Ion beam methods (triode setups):**
 - **Ion beam milling (IBM),**
 - Reactive ion beam etching (RIBE),
 - Chemical assisted ion beam etching (CAIBE).
 - Deep Reactive Ion Etching (DRIE).
- Wet etching (chemical liquids).



https://en.wikipedia.org/wiki/Focused_ion_beam

Focused stream of ions, e.g. gallium
Sputtering/milling

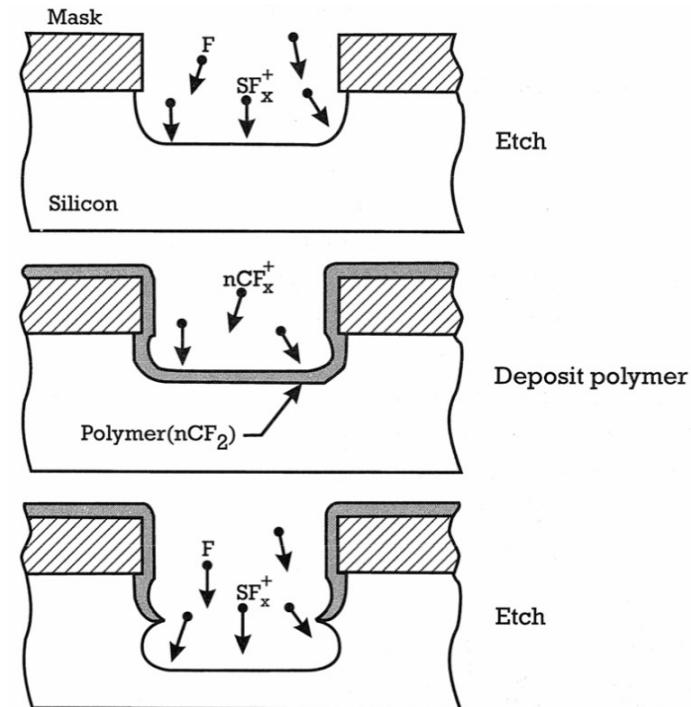
3. SUBTRACTIVE PROCESSES

- Dry etching (plasma):
 - Glow discharge methods (diode setups):
 - Plasma etching (PE),
 - Reactive ion etching (RIE),
 - Ion beam methods (triode setups):
 - Ion beam milling (IBM),
 - Reactive ion beam etching (RIBE),
 - Chemical assisted ion beam etching (CAIBE).
 - **Deep Reactive Ion Etching (DRIE).**
- Wet etching (chemical liquids).

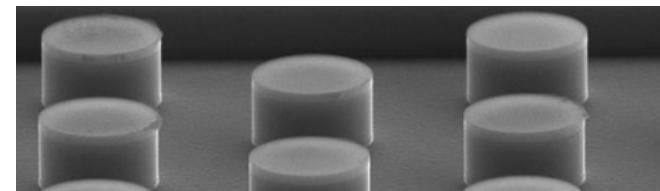


**TAL
TECH**

TALLINN UNIVERSITY
OF TECHNOLOGY



<https://www.micronit.de/technologies/dry-etching-drie/>

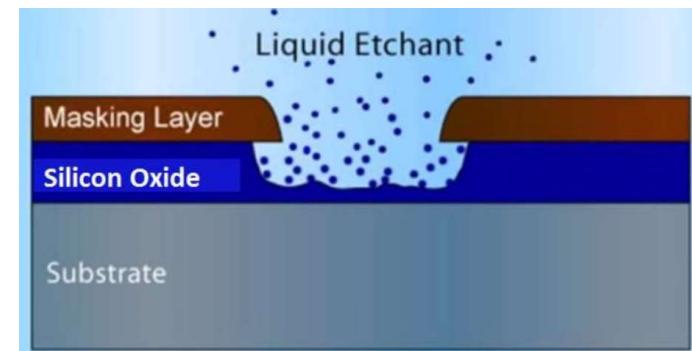


Source: Maluf 2005

13.01.2022

3. MICROFABRICATION PROCESSES

- Dry etching (plasma):
 - Glow discharge methods (diode setups):
 - Plasma etching (PE),
 - Reactive ion etching (RIE),
 - Ion beam methods (triode setups):
 - Ion beam milling (IBM),
 - Reactive ion beam etching (RIBE),
 - Chemical assisted ion beam etching (CAIBE).
 - Deep Reactive Ion Etching (DRIE).
- **Wet etching (chemical liquids).**

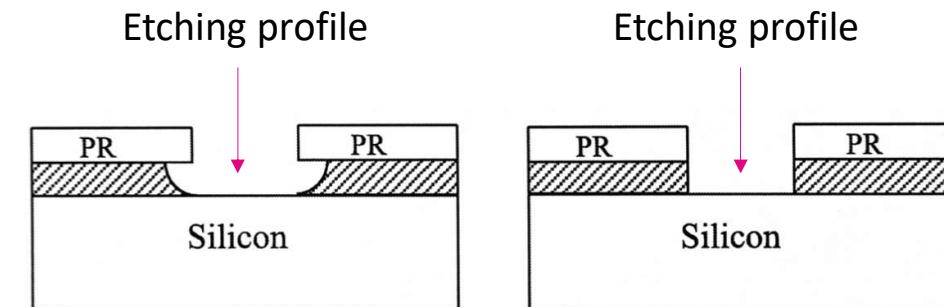


Done using aggressive chemicals, e.g.
NaOH, KOH, HF, BF_3 , BCl_3



ALWAYS USE PROTECTIVE CLOTHING AND OBSERVE SAFETY INSTRUCTIONS!

3. MICROFABRICATION PROCESSES



Isotropic Etching

Anisotropic Etching

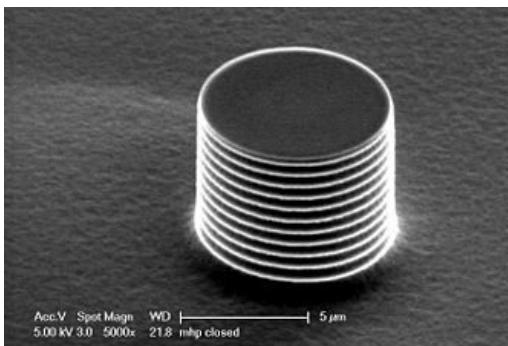
Wet etching typically has isotropic etching profiles

DRIE is highly anisotropic, but only achieves this via cyclic passivation

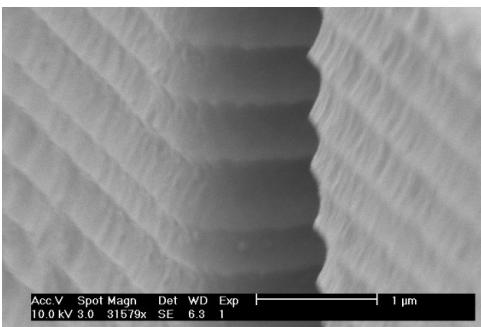


3. MICROFABRICATION PROCESSES

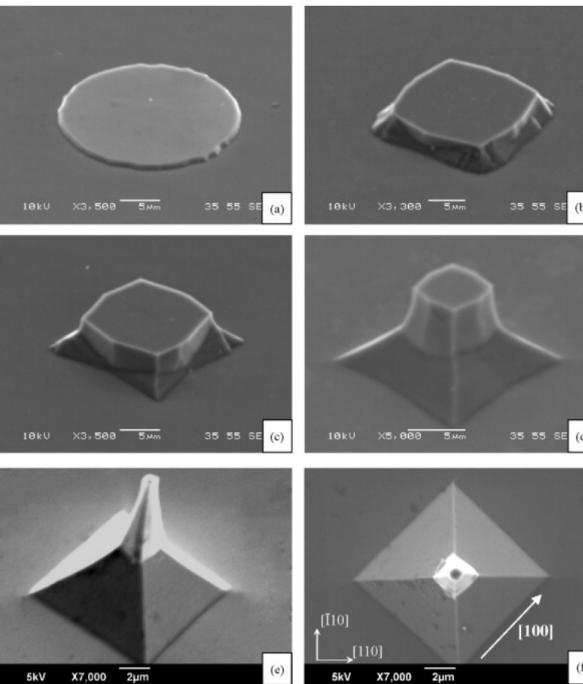
DRIE



https://en.wikipedia.org/wiki/Deep_reactive-ion_etching



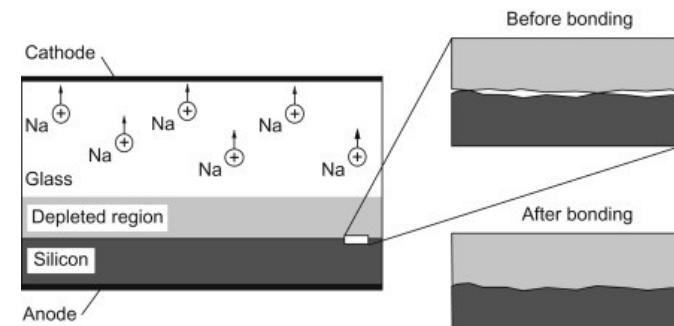
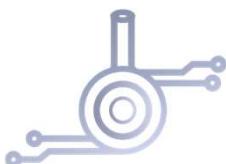
Anisotropic wet etching



<https://www.sciencedirect.com/science/article/pii/S0924424709001526#fig3>

3. MICROFABRICATION PROCESSES

- **Chip bonding:**
 - you need to bond the two halves of the chip together to seal it
- **Direct bonding:**
 - Anodic bonding of silicon to glass
 - Silicon direct bonding
- **Intermediate adhesive layers**
 - Thermoplastics
 - Solvents
 - Double-sided tape ☺
- **Welding**
 - Laser welding
 - Ultrasonic welding
 - Diffusion welding



<https://www.sciencedirect.com/science/article/pii/B9780323299657000300>



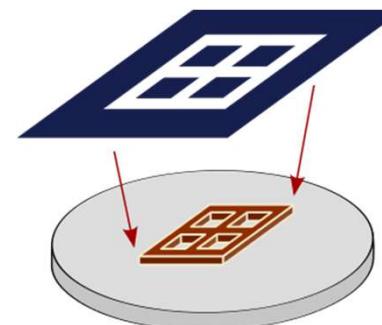
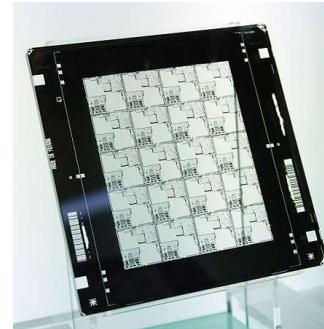
3. MICROFABRICATION PROCESSES

▪ Photolithography:

- Used for selective etching of oxide layers
- Needs a photomask
- Positive photoresist: soluble where exposed
- Negative photoresist: insoluble where exposed

▪ Process:

- Cleaning and preparation of wafer
- Application of photoresist by spin coating and prebaking at 90-100 °C, 30-60 s
- Mask alignment
- Exposure to UV light
- Post-exposure bake at 120-180 °C, 20-30 min and then develop. Wash away soluble resist.
- Etch exposed oxide (wet or dry)
- Remove resist residue.



- Prepare wafer

oxide	
substrate	
- Apply photoresist

PR	
oxide	
substrate	
- Align photomask

glass	
Cr	
PR	
oxide	
substrate	
- Expose to UV light

glass	
Cr	
PR	
oxide	
substrate	
- Develop and remove photoresist exposed to UV light

PR	
oxide	
substrate	
- Etch exposed oxide

PR	
oxide	
substrate	
- Remove remaining photoresist

oxide	
substrate	

3. MICROFABRICATION PROCESSES

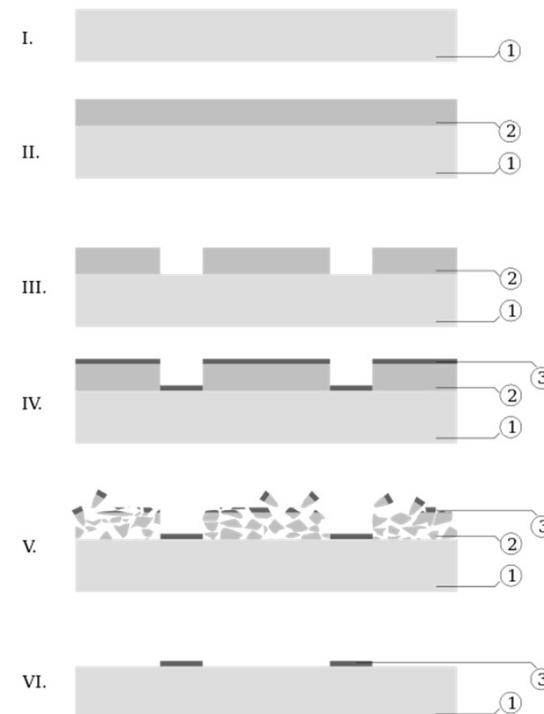
- **Photolithography and lift-off process**

1. Preparation of the substrate
2. Deposition of the sacrificial stencil layer
3. Patterning the sacrificial layer (ex. etching), creating an inverse pattern
4. Deposition of the target material
5. Washing out the sacrificial layer together with the target material on its surface

- **Pattern Layers:**

1. Substrate
2. Sacrificial layer
3. Target material

- **Mostly used to create metallic interconnections.**



By Twisp - Own work, Public Domain,
<https://commons.wikimedia.org/w/index.php?curid=3841773>

4. MICROFABRICATION OF LAB-ON-A-CHIP DEVICES

▪ SU8 soft lithography

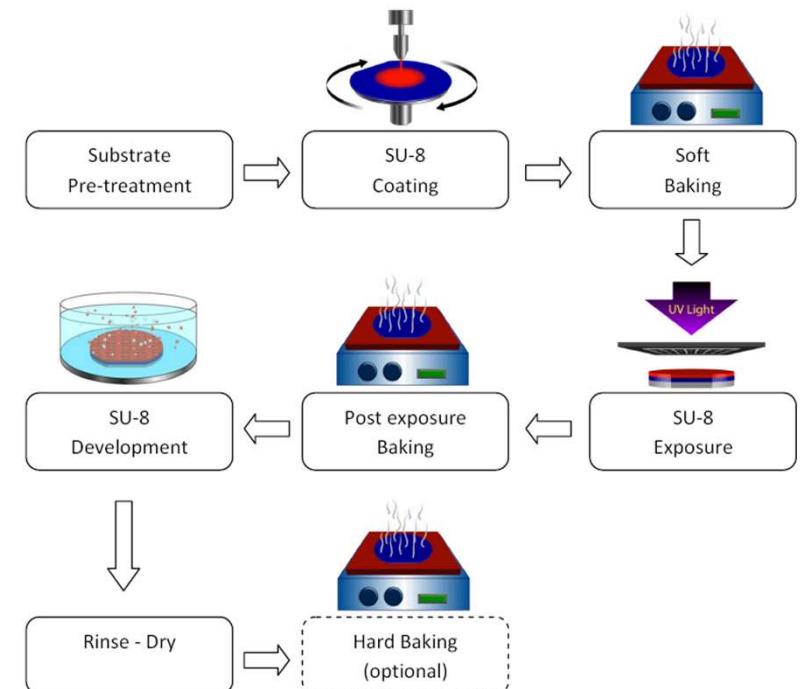
- negative
- thick resist (thickness up to 0.5 mm or even 1 mm)
- can be used for molding PDMS

▪ Advantages: cheaper instrumentation

- Clean room not needed
- Reasonable instrumentation cost (50-100k€)
- Minimally spin coater, hot plate, mask aligner or LDI system needed
- LDI (laser direct imaging) doesn't need a mask, uses UV laser to expose resist
- Produces structures with good aspect ratios

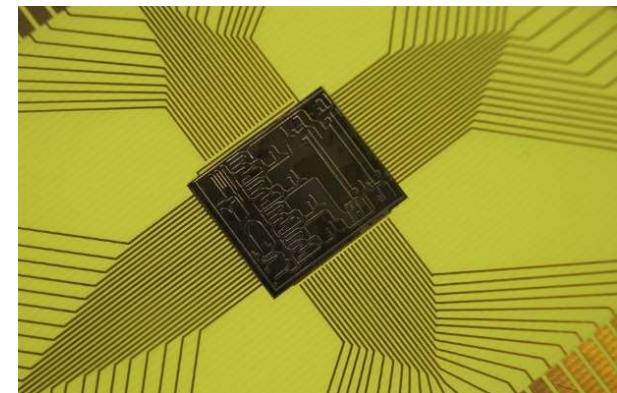
▪ Disadvantages: lower quality than Si masks

- Resolution & mold lifetime lower than with silicon molds
- Silicon-glass or glass-glass chips are far more robust



4. MICROFABRICATION OF LAB-ON-A-CHIP DEVICES

- **Silicon-glass and glass-glass chips**
- **Process:**
 - One or both sides are structured with surface and/or bulk micromachining
 - The two sides are bonded together
- **Advantages:**
 - Very high aspect ratio
 - Possibility to integrate electronics
 - Excellent process control
- **Disadvantages:**
 - Initial investment is huge
 - Only makes sense in professional market
- Both silicon and glass can be combined with hard polymers too





MICROFABRICATION PROCESSES

- Additive processes
- Subtractive processes
- Soft lithography

13.01.2022



COMMERCIAL EXAMPLES

- Immunoassays
- Nucleic acid amplification tests

13.01.2022

IMMUNOASSAY VS. NAAT

■ Immunoassay:

- biochemical test that measures the presence/concentration of a molecule in a solution using an antibody/antigen.
- Detects an already present immune response
- This needs a few days – few weeks time!
- In the case of infectious diseases, the host keeps infecting during the incubation time, not knowing about their infection...**

■ Nucleic acid amplification test:

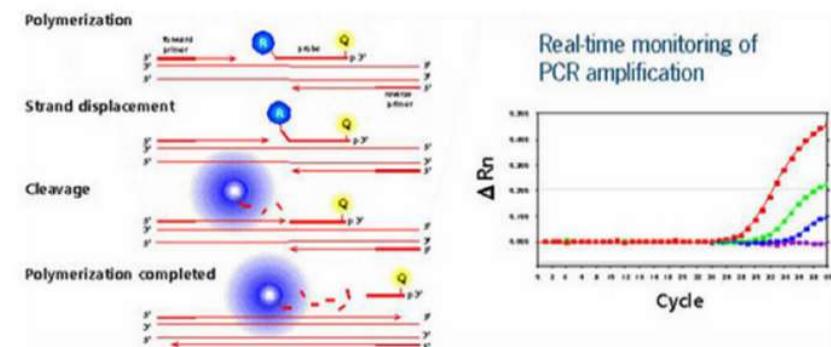
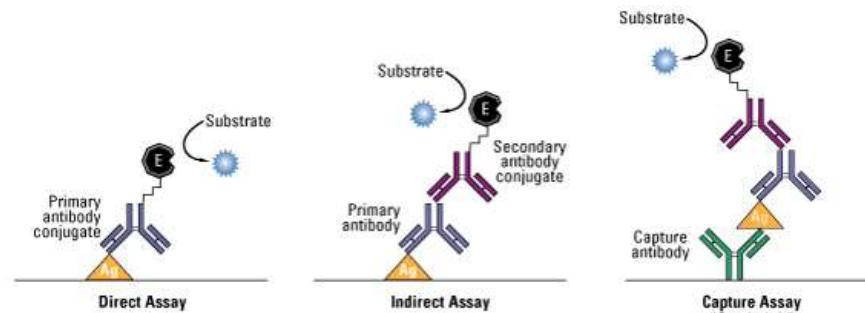
- a molecular technique to detect a target pathogen in a specimen, typically a body fluid, by amplifying the concentration of its DNA/RNA (bacteria/viruses)
- Instantaneous, extremely sensitive & specific**



**TAL
TECH**

TALLINN UNIVERSITY
OF TECHNOLOGY

<https://www.thermofisher.com/content/dam/LifeTech/global/life-sciences/protein-biology/PBLC/1499003520217.jpg>
<https://www.intechopen.com/source/html/49685/media/fig1.png>



13.01.2022



DMF: ILLUMINA NEOPREP

- **NeoPrep NGS Library Prep with Digital Microfluidics**
 - **Platform:** PCB two-plate DMF with filler fluid
 - **Product:** Next generation sequencing tool for DNA sequencing and library preparation
 - **Input:** various
 - **Output:** genome library
 - Now Illumina, was: Advanced Liquid Logic LLC
 - Genome library: collection of genomic DNA from a single organism
- **Links:**
 - https://youtu.be/F_Hks6OnSKM
 - <https://www.illumina.com/science/technology/digital-microfluidics.html>
 - <https://www.illumina.com/content/dam/illumina-marketing/documents/products/brochures/brochure-neoprep.pdf>



Technical challenges in DMF....

! Illumina no longer accepts orders for the NeoPrep System. October 31, 2017. For alternative solutions, see our [library](#) to providing you with high quality support and service.

13.01.2022

1. Flow chemistry

2. Cartridge + reader

3. True Lab-on-a-Chip

MCHIP

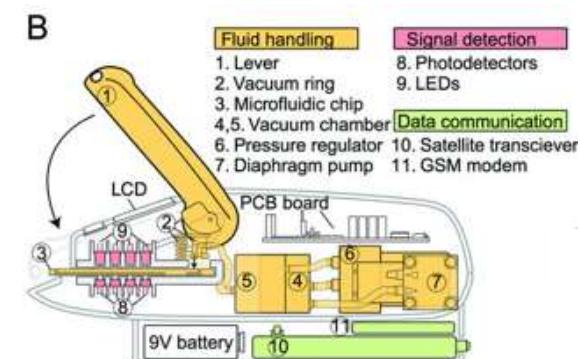
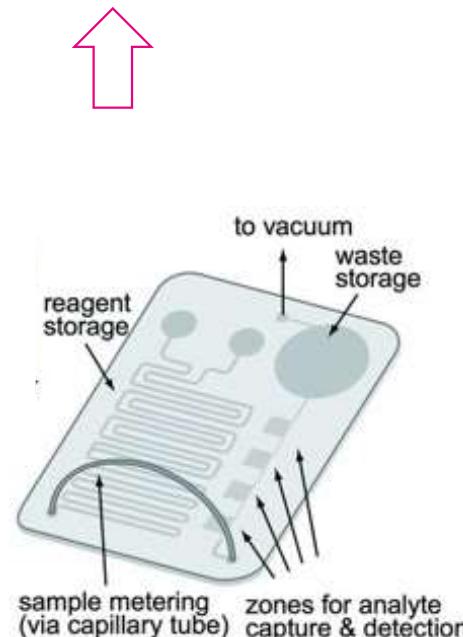
System:

- **Platform:** Injection moulded plastic CMF chip
- **Product:** portable HIV-1 ELISA blood test
- **Input:** blood
- **Output:** digitized optical readout
- **Assay time:** 20 min

Functions

- Immunoassay test (requires 2-4 week incubation)
- **CMF Actuation: Negative pressure driven flow**
- Optical readout
- Wireless data reporting (result + GPS coordinates)
- Size: 11 cm x 7 cm x 24 cm

<http://www.nature.com/nm/journal/v17/n8/full/nm.2408.html>
<https://en.wikipedia.org/wiki/MChip>
<https://www.youtube.com/watch?v=vpxnJM2jSVg>



MCHIP

	Benchtop ELISA				Rapid test	mChip
	Liquid \ddagger handling	Signal # detection	Data processing & \wedge communication	Total	Total	Total
Space of device (in 3)	2380	2170	1170	5720	NA	180
Power of device (W)	150	300	50	500	NA	0.6
Cost of device (USD)	\$9600	\$8850	\$1000	\$19450	NA	<\$1000*
Market price per test (USD)	1.80 to 6.20			0.40 to 4.50	1.00 to 3.00**	
Reagent volume/test (μ L)	4400 \dagger			50 to 900	160	
Sample volume/test (μ L)	75 \dagger			10 to 80	0.2	
Time to run assay (min)	130 \dagger			10 to 30	20	
Time from sample collection to results (min)	150 \dagger			10 to 30	20	
Sample throughput/day	Hundreds			Tens	Tens	
Objective interpretation of results	Yes			No	Yes	
Communicates with EMRs	Yes			No	Yes	
Handles whole blood	No			Yes	Yes	

‡ Biotek Microplate Washer ELx405 # Biotek Microplate Reader ELx808 ^Dell Latitude E6400

† Bio-Rad Genetic Systems HIV-1/HIV-2 PLUS O Enzyme Immunoassay (FDA-approved)

* estimated manufacturing cost ** estimated

© 2010 Pearson Education, Inc. All Rights Reserved. May not be reproduced, displayed, or transmitted, in whole or in part, in any form, without the prior written permission of the author.



TAL TECH

TALLINN UNIVERSITY OF TECHNOLOGY

When to use microfluidics (professional):
If you can make it cheaper...

Not just cheaper but...

- More widely available
- Smaller device size
- Smaller sample size ($0.2 \mu\text{l}$)
- Smaller reagent size
- Easier to use (minimal training)
- Faster detection

13.01.2022

1. Flow chemistry

2. Cartridge + reader

3. True Lab-on-a-Chip

PERKINELMER LABCHIP GX TOUCH 24

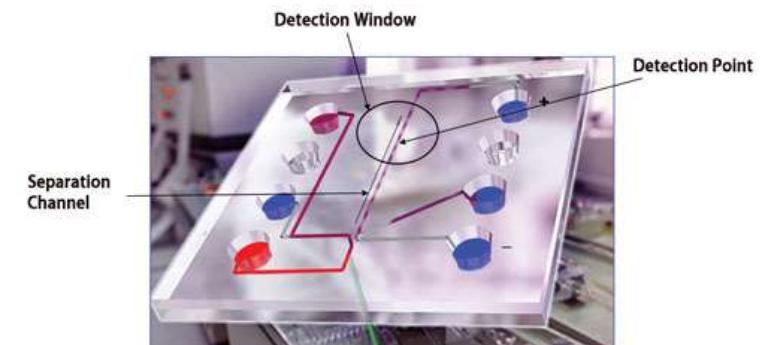
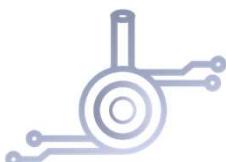


- **PerkinElmer LabChip GX Touch 24**

- **Platform:** plastic CMF chip
- **Product:** Microfluidic capillary electrophoresis system for DNA/RNA quantification
- **Input:** free DNA in liquid
- **Output:** (digital) quantified DNA
- **Assay time:** 30 seconds

- **Links:**

- <http://www.perkinelmer.co.uk/product/24-labchip-gx-touch-cls138162>



1. Flow chemistry

2. Cartridge + reader

3. True Lab-on-a-Chip

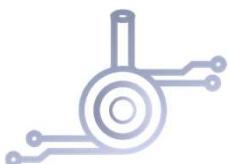
ABBOTT I-STAT HANDHELD

▪ i-STAT handheld

- **Platform:** Injection moulded CMF chips with electrochemical detector
- **Product:** Immunoassay cartridges + handheld reader
- **Input:** blood
- **Output:** electrochemical readout
- **Assay time:** 2-3 minutes

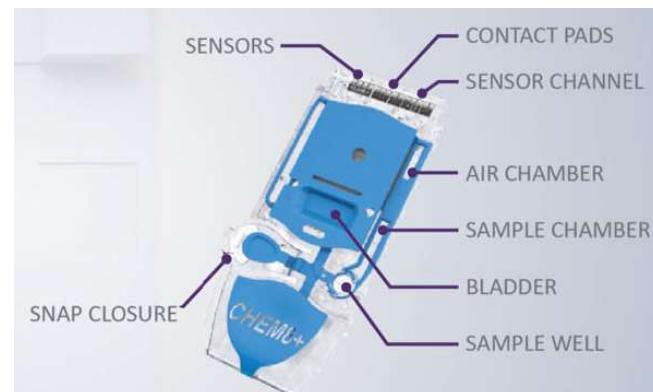
▪ Links:

- <https://www.pointofcare.abbott/int/en/offerings/istat/istat-handheld>
- https://www.pointofcare.abbott/download?docUri=/technical-library/static-assets/technical-documentation/4_Section_2_Testing_Pro_for_iSTAT_Chem_Cart_725592-00K.pdf



**TAL
TECH**

TALLINN UNIVERSITY
OF TECHNOLOGY



13.01.2022

1. Flow chemistry

2. Cartridge + reader

3. True Lab-on-a-Chip

SIMBAS CHIP

- **Stand-alone self-powered integrated microfluidic blood analysis system (SIMBAS)**

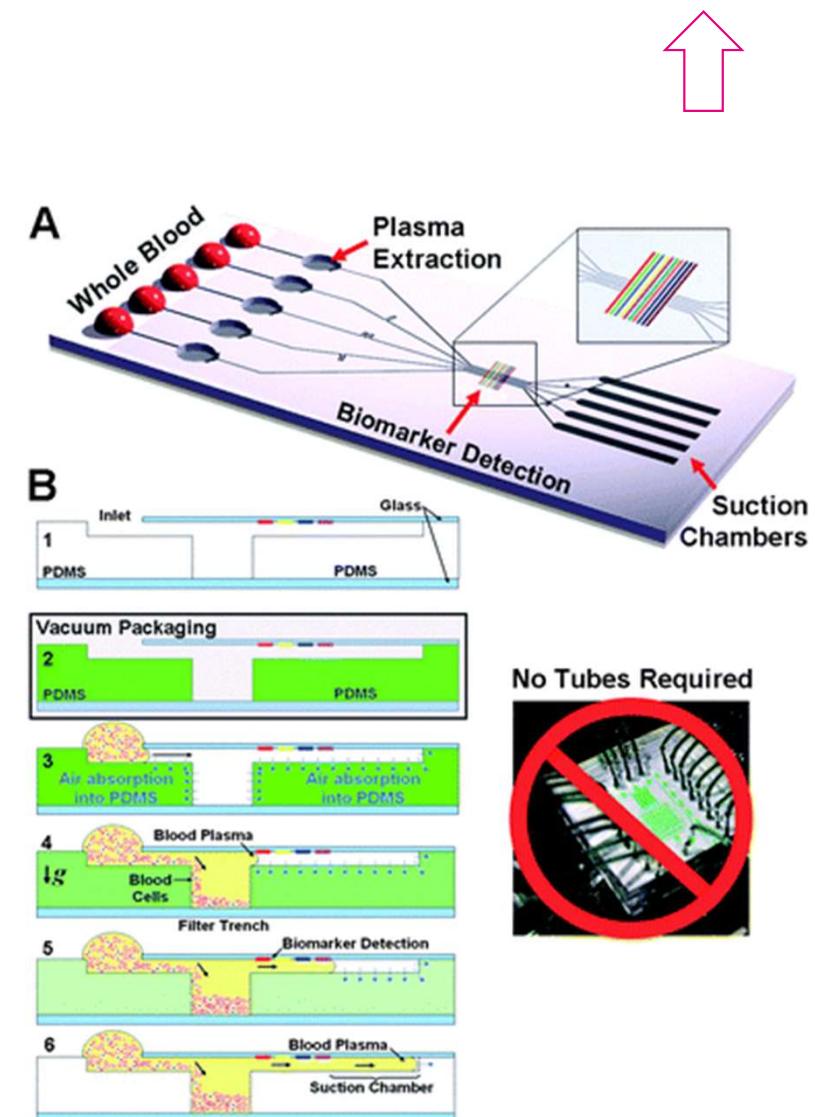
- **Platform:** PDMS-glass CMF chip
- **Product:** portable blood test
- **Input:** 5 μ l blood droplet
- **Output:** optical readout (colorimetry)
- **Assay time:** 10 min

- **System:**

- Chip is vacuum-sealed and sucks in sample when opened
- On-chip cell separation and plasma extraction

- **Link:**

- <http://pubs.rsc.org/en/content/articlehtml/2011/lc/c0lc00403k>



1. Flow chemistry

2. Cartridge + reader

3. True Lab-on-a-Chip



STD MULTITEST

▪ STD Multitest

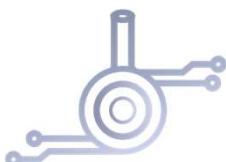
- **Platform:** All-in-one plastic CMF chip
- **Product:** 2nd generation RDT for the detection of sexually transmitted diseases
- **Input:** urine
- **Output:** lateral flow strip visualization
- **Assay time:** 30 minutes
- Non-instrumented nucleic acid amplification test (NINAAT) – single-use, self-contained DNA amplification platform
- Results are on par with laboratory assays



<http://selfdiagnostics.com/std-multitest/>

▪ Links:

- <http://selfdiagnostics.com/std-multitest/>
- <http://selfdiagnostics.com/technology/>



**TAL
TECH**

TALLINN UNIVERSITY
OF TECHNOLOGY

 **99.9%**
PPV

 **98.1%**
NPV

13.01.2022

1. Flow chemistry

2. Cartridge + reader

3. True Lab-on-a-Chip

LUCIRA CHECK-IT EASY



- **Lucira Covid-19 test kit**
 - **Platform:** All-in-one plastic CMF chip
 - **Product:** 2nd generation RDT for the detection of sexually transmitted diseases
 - **Input:** Nasal swab
 - **Output:** Colorimetry
 - **Assay time:** 11 minutes for positive result, 30 minutes for negative result
 - FDA EUA approved
- **Links:**
 - [Lucira Check It COVID-19 All-In-One Test Kit – LUCIRA \(lucirahealth.com\)](https://lucirahealth.com)
 - [Lucira COVID-19 Test Kit Demonstration - YouTube](https://www.youtube.com/watch?v=JyfJLJLJLjU)





COMMERCIAL EXAMPLES

- Immunoassays
- Nucleic acid amplification tests

13.01.2022



**TAL
TECH**

IEE1860 BIOMEMS

Contact: tamas.pardy@taltech.ee

**TALLINN UNIVERSITY
OF TECHNOLOGY**



BIOMEMS

self
diagnostics

